



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1756**

Application Number: **10/670,291**

Examiner: **Daborah Chacko-Davis**

Filed: **September 26, 2003**

Confirmation Number: **6427**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR  
FORMING RESIST PATTERN, AND PROCESS FOR  
MANUFACTURING SEMICONDUCTOR DEVICE**

Attorney Docket Number: **031181**

Customer Number: **38834**

**INFORMATION DISCLOSURE STATEMENT**  
**UNDER 37 C.F.R. 1.97(c)(2)**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

August 21, 2007

Sir:

Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached PTO/SB/08. A copy of each non- U.S. document is attached.

This Information Disclosure Statement is being submitted after issuance of a first official action on the merits and expiration of the three month period following the filing date or the entry of the national stage for the above-captioned application, but prior to issuance of either a final official action or a Notice of Allowance. A check is attached hereto which covers the \$180.00 fee set forth in 37 C.F.R. §1.17(p).

08/22/2007 MAHME1 00000049 10670291

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180.00 OP

Information Disclosure Statement under 1.97(c)(2)

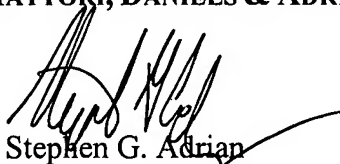
Attorney Docket No. 031181

Serial No. 10/670,291

If there are any fees due in connection with the filing of this paper, please charge Deposit  
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Respectfully submitted,

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Enclosures: PTO/SB/08  
3 Documents  
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Combined Form PTO/SB/08A&amp;B

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Complete if Known

Application Number	10/670,291
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First Named Inventor	Miwa KOZAWA et al.
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Examiner Name	Daborah Chacko-Davis
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Sheet

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of

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**U.S. PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code <sup>2</sup> (if known)		
		US			
		US			
		US			

**FOREIGN PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Translation <sup>6</sup>
		Country Code <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)			

**NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation <sup>6</sup>
	1	TAKEO ISHIBASHI ET AL., Advanced Micro-Lithography Process with Chemical Shrink Technology, Japanese Journal of Applied Physics Vol. 40 (2001) pp. 419-425	
	2	MAMORU TERAII ET AL., Below 70-nm Contact Hole Pattern with RELACS Process on ArF Resist, Advances in Resist Technology and Processing XX, Theodore H. Fedynyshyn, Editor, Proceedings of SPIE Vol. 5039 (2003)	
	3	MAMORU TERAII ET AL., Newly Developed Resolution Enhancement Lithography Assisted by Chemical Shrink Process and Materials for Next-Generation Devices, Japanese Journal of Applied Physics Vol. 45, No. 6B (2006) pp. 5354-5358	

Examiner Signature

Date Considered

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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